



- 30 -

Exposure control circuit, 73...Laser length measuring machine, 74...Distribution circuit, 75a, 75b...Buffer memory, 76...Selection circuit.

5 The present invention permits correction of the pattern data to be performed in the phase of preparing the pattern data. The pattern data generation and storage speed may be kept at one tenth through one hundredth the speed for reading and writing the data. So the size of the circuit can be reduced to one tenth
10 through one hundredth that in the case where pattern data is corrected. Thus, the cost reduction achieved by the present invention provides a drastic effect.